

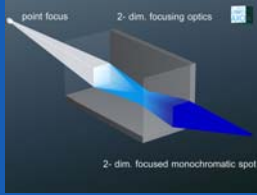
## X-Ray analytical application of multilayer X-ray optics

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### ASTIX-f – Optics for micro focusing



Beam path and monochromatization of a focusing ASTIX-f system

#### Advantages of the ASTIX-solution

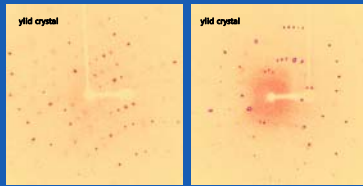
Symmetric spot geometry in the focal plane even for highly asymmetric source dimensions

Improved lateral and temporal homogeneity

Wide variety in spot dimension of less than 30µm to more than 300µm on fixed anode and micro focus X-ray tubes depending on multilayer system, deposition and geometry parameters

Typical mirror length up to 150 mm

Improved P/B ratio due to reduced scattered background



arrangement 1: µ-source (Mo) coupled with ASTIX-f\*

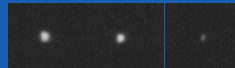
arrangement 2: Fixed anode tube (Mo) coupled with HOPG\*

Resolution A	measured offset	best offset	average intensity	P/B ratio	Rate
180-1.180	500	500	5.5	60.26	0.014
180-1.180	600	600	6.0	58.05	0.015
180-1.180	700	700	6.2	56.88	0.016
180-1.180	800	800	6.1	56.94	0.016
180-1.180	900	900	7.2	53.01	0.017
180-1.180	1000	1000	6.8	51.72	0.018
180-1.800	500	500	5.1	58.75	0.011
180-1.800	600	600	5.1	57.95	0.011
180-1.800	700	700	5.3	56.88	0.011
180-1.800	800	800	5.6	54.1	0.012
180-1.800	900	900	5.4	53.15	0.013

Table: Results of data collection (YLiF crystal); completeness > 99 %  
\* data of ylid single crystal diffraction by courtesy of Oxford Diffraction

ASTIX 150 and ASTIX 100 with vacuum mirror housing AMH100 and AMH150

∅ > 300µm ∅ < 100µm



Symmetric shape of secondary focal spots with ∅ < 100µm up to ∅ > 300µm measured at fixed anode tubes (Cu) coupled with ASTIX-f (marcam images)

### Modular X-ray system (micro source + ASTIX-f optics) applicable both for standard XRD (powder diffraction / SCD) and micro diffraction



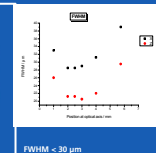
FWHM < 150 µm

Geometry 100/300:  
∅ = 150 µm  
∅ = 7.5 × 10<sup>8</sup> cps

Mo Kα Microfocus X-ray source (spot ∅ 50 µm @ 30 W) and ASTIX-F100



Geometry 300/100:  
∅ = 28 µm × 21 µm  
∅ = 2.5 × 10<sup>9</sup> cps



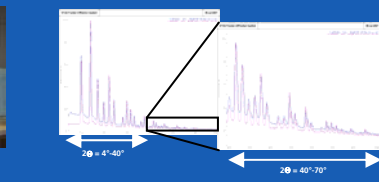
FWHM < 30 µm

### µ-focus MoKα source coupled with ASTIX-f (a) vs. X-ray tube + HOPG + capillary (b)



STOE powder diffraction system  
LaB<sub>6</sub> powder sample / capillary ∅ 250 µm  
time: 3 min / image plate detector

setup:  
(a) spot size: 150 µm  
cone angle: 3 mrad  
(b) spot size: 300 µm  
cone angle: 7 mrad



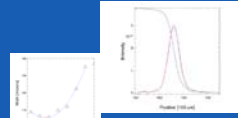
Results with ASTIX-f:

- highly symmetric spot at sample position
- low background intensity
- twice the flux density in a 150 µm spot
- nearly the same peak intensity with reduced illuminated sample volume
- higher resolution (K<sub>α</sub> splitting)
- increased P/B ratio with ASTIX-f solution
- higher efficiency due to precise application

### Combination of sealed X-ray source with ASTIX-c (L=60) for Cr Kα



Cr Kα sealed tube X-ray source (spot 1.2x0.4 / 1.2kV) and ASTIX-c 60 ∅ / 150

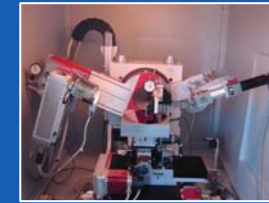


Geometry ∅ 150:  
Beam profile: ∅ = 100µm (FWHM)  
1 × 1 × 10<sup>9</sup> cps (Cr Kα)  
Long distance focussing  
Measurement up to 2θ > 160°

### Ag Kα parallel beam optics for X-Ray diffraction

#### Goal

- covering a large q-range up to 20 Å<sup>-1</sup> in the reciprocal space (0.1° < 2θ < 160°)
- high penetration depth also in metal samples
- reduced influence of sample fluorescence, displacement errors and sample transparency in parallel beam geometry with secondary monochromator

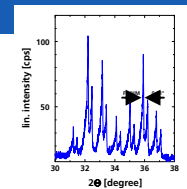
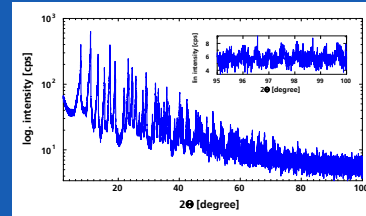


experimental setup:  
Diffractometer XRD 3003 (Gö-11) for samples up to 200 mm × 200 mm or 8" ∅ and for measurements up to 2θ = 160°

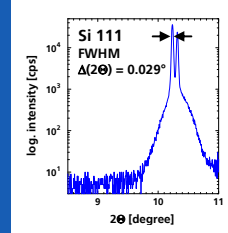


Parallel beam profiles without (a) and with sample (b) in the beam path (LaB<sub>6</sub> capillary ∅ 500 µm)

### XRD measurements of LaB<sub>6</sub> powder sample (50kV / 25mA)



### XRD measurement of single crystal Si111 reflection



#### Results:

- intensity > 10<sup>8</sup> cps
- I(Ag Kα) : I(Ag Kβ) > 10.000
- beam divergence Δθ ≈ 0.015° (< 60 arcsec)
- improved P/B ratio due to suppression of other characteristic emission lines (Ag Kβ)
- low background intensity level (< 5 cps)
- reflexions up to 2θ = 100° detected at LaB<sub>6</sub>

### Multilayer Monochromators for Synchrotron Applications

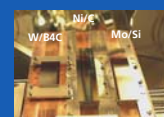


- Application : from EUV to hard X-rays (< 50 eV – 100 keV)
- Material systems : optimized on wavelength and bandwidth on customers' request
- Dimensions : up to 8" diameter or up to 500 mm in length
- Thickness homogeneity: Δd < 0.002 nm for d = 1 nm (Δd/d < 0.2%)
- Resolution: 0.25% < ΔE/E < 10%

### Stability of Ni/C multilayer



- water cooled  
Ni/C (IW5): d = 3.38 nm  
100 layers  
Γ = 0.45  
ΔE/E = 2 × 10<sup>-2</sup>  
deposited on Si-mirrors (Zeiss)  
size 120 × 30 × 10 mm<sup>3</sup>  
energy range: 3-8 keV and 10-100 keV



- Results:  
Ni/C multilayer used as DMM (HASYLAB at DESY)  
Physical life: 1.5 a / effective 4 months  
Energy range: 12 keV, 18 keV, 40-60 keV / water cooling  
Vacuum: base pressure 1 × 10<sup>-4</sup> mbar  
Results of Cu Kα reflectometry: No remarkable decrease of reflected peak intensities at both multilayers  
WH1: increase of mean period thickness about 0.15 nm  
Higher heat load at mirror WH1 up to a temperature of approx. 200°C



WH 1: close to source



WH 2